



Cold Atmospheric Plasma: Sources, Processes, and Applications

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Message from the Guest Editors

Dear Colleagues,

Cold atmospheric plasma (CAPs) have earned their place within the broader field of plasma technology, branching out in many other major disciplines, including catalysis, biomedical engineering, medicine, energy applications, waste treatment, agriculture, etc., thanks to their versatility in design, ease of implementation, low cost and unique chemical composition.

This Special Issue in particular will focus on CAPs used for surface modification processes. Surface and interface enhancement of materials in general continues to generate a lot of interest in any discipline, as it allows to maintain interesting bulk material properties of low-tech materials such as strength, weight and elasticity while making them suitable for high-tech applications.

The overall goal of this Special Issue is to cover the employed plasma sources, the innovative processes under development, the envisioned applications and the future challenges to be tackled by the scientific community.

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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

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